

<b>Notice of References Cited</b>	Application/Control No. 10/795,915		Applicant(s)/Patent Under Reexamination CHANG ET AL.	
	Examiner Kara E. Geisel		Art Unit 2877	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-2002/0038196	03-2002	Johnson et al.	702/179
*	C	US-2004/0070772	04-2004	Shchegrov et al.	356/625
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

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	U	Bischoff et al., "Characterization of 3D resist patterns by means of optical scatterometry", May 1999, SPIE, Vol. 3743, pages 49-60.
	V	Yeung et al., "Electromagnetic Scatterometry Applied to In Situ Metrology", 2001, SPIE, Vol. 4344, pages 484-495.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.